

**Search Notes****Application/Control No.**

10/721,230

**Examiner**

Stephen W. Smoot

**Applicant(s)/Patent under Reexamination**

SATO ET AL.

**Art Unit**

2813

**SEARCHED**

Class	Subclass	Date	Examiner
257	510	7/11/2005	SWS
257	622	7/11/2005	SWS
257	635	7/11/2005	SWS
438	296	7/11/2005	SWS
438	424	7/11/2005	SWS
438	435	7/11/2005	SWS
438	763	7/11/2005	SWS
438	781	7/11/2005	SWS
438	782	7/11/2005	SWS
438	926	7/11/2005	SWS

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Considered all citations from parent application except for KR 1994-0004776.	7/11/2005	SWS
Key Words: Patterns - Gate, Dummy; Trench, Groove; Insulator, Dielectric; SOG - Spin-on Glass, Polysilazane;	7/11/2005	SWS
CVD - Chemical Vapor Deposition; Gap Filling.	7/14/2005	SWS
Search Tools - EAST (attached); USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	7/11/2005	SWS